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APPLICATION N	10.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/611,037		07/06/2000	Andras Kuthi	LAM1P077A	5329
25920	7590	10/08/2003		EXAMINER	
		NILLA, LLP	ALEJANDRO M	ALEJANDRO MULERO, LUZ L	
710 LAKEWAY DRIVE SUITE 170				ART UNIT	PAPER NUMBER
SUNNYVALE, CA 94085				1763	
		DATE MAILED: 10/08/2003			3

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)				
*	00/614 027	ì				
Advisory Action	09/611,037	KUTHI ET AL.				
	Examiner	Art Unit				
The MAILING DATE of this communication on	Luz L. Alejandro	1763				
The MAILING DATE of this communication ap	pears on the cover sneet with the c	corresponaence add	ress			
THE REPLY FILED 04 September 2003 FAILS TO PLACE THIS APPLICATION IN CONDITION FOR ALLOWANCE. Therefore, further action by the applicant is required to avoid abandonment of this application. A proper reply to a final rejection under 37 CFR 1.113 may only be either: (1) a timely filed amendment which places the application in condition for allowance; (2) a timely filed Notice of Appeal (with appeal fee); or (3) a timely filed Request for Continued Examination (RCE) in compliance with 37 CFR 1.114.						
PERIOD FOR REPLY [check either a) or b)]						
 a)	s Advisory Action, or (2) the date set forth e later than SIX MONTHS from the mailin	g date of the final rejection	on.			
Extensions of time may be obtained under 37 CFR 1.136(a). To fee have been filed is the date for purposes of determining the periodic fee under 37 CFR 1.17(a) is calculated from: (1) the expiration date (2) as set forth in (b) above, if checked. Any reply received by the Ottimely filed, may reduce any earned patent term adjustment. See 37	d of extension and the corresponding amo of the shortened statutory period for reply office later than three months after the mai	ount of the fee. The appropriate originally set in the final	opriate extension Office action; or			
1. A Notice of Appeal was filed on Appellant's Brief must be filed within the period set forth in 37 CFR 1.192(a), or any extension thereof (37 CFR 1.191(d)), to avoid dismissal of the appeal.						
2. The proposed amendment(s) will not be entered because:						
(a) They raise new issues that would require further consideration and/or search (see NOTE below);						
(b) they raise the issue of new matter (see Note	e below);					
(c) They are not deemed to place the application in better form for appeal by materially reducing or simplifying the issues for appeal; and/or						
(d) they present additional claims without canceling a corresponding number of finally rejected claims. NOTE: .						
3. Applicant's reply has overcome the following reje	ection(s):					
4. Newly proposed or amended claim(s) wou canceling the non-allowable claim(s).	ld be allowable if submitted in a se	eparate, timely filed	amendment			
5.⊠ The a) affidavit, b) exhibit, or c) request for application in condition for allowance because:		idered but does NO	Γ place the			
6. The affidavit or exhibit will NOT be considered be raised by the Examiner in the final rejection.	ecause it is not directed SOLELY t	to issues which were	e newly			
7. For purposes of Appeal, the proposed amendme explanation of how the new or amended claims			ınd an			
The status of the claim(s) is (or will be) as follows	3:					
Claim(s) allowed:						
Claim(s) objected to:						
Claim(s) rejected:						
Claim(s) withdrawn from consideration:						
8. The proposed drawing correction filed on	is a)☐ approved or b)☐ disapp	proved by the Exami	ner.			
9. Note the attached Information Disclosure Statem	, , , , , , , , , , , , , , , , , , , ,	•				
10. Other:	()	 -	_			
		Luz L. Alejandro Primary Examiner Art Unit: 1763	W			

Continuation of 5. does NOT place the application in condition for allowance because:

Regarding the rejection under 35 USC 112, second paragraph, the examiner respectfully submits that the term "high aspect ratio" has not been defined by the specification with sufficient specificity so that one of ordinary skill in the art could determine the metes and bound of the claims which include this term. Also note that what is meant by the term "high aspect ratio" can vary from disclosure to disclosure, so the fact that this is mentioned in one disclosure does not mean that the term has the same definition in the instant application. For these reasons, this rejection is maintained.

With respect to the rejections under 35 USC 103, note that the declaration under 37 CFR 1.132 has not been presented in a timely manner and therefore will not be given consideration at this late stage of the prosecution. Furthermore, note that the examiner's rationale for inherency was gleaned from applicant's disclosure at page 13, lines 22-24 when applicant states that "Because the electrode opening 202b have increased to be at least equal to or greater than about 0.5mm, a plasma sheath 231 is caused to shift into the electrode openings 202b.". Again, for these reasons, it is believed that the examiner has provided a prima facie inherency argument which has not been effectively rebutted by applicant. Regarding the Tomita et al. reference, the small openings in the cathode plate have a dimension o 0.6mm which, according to applicant's specification, is sufficiently large to allow plasma to shift into these holes, whether this effect is desirable or not. Concerning the use of the Chang et al. reference and combining this reference with the Tomita et al. reference, it does not appear that modifying Tomita et al. with Chang will render Tomita et al. unsatisfactory for its intended purpose, since the portion relied upon by applicant (col. 2-lines 46-52 of Tomita et al.) is intended only to prevent a polymer by-product resulting from the plasma from being in the small hole and says nothing about preventing plasma itself. In fact, it appears that it is the speed of the gas in the hole which suppresses the deposition of the polymer, and a link between plasma flowing in the hole and polymer deposition has not been made. Furthermore, the examiner believes the motivation to combine the Tomita et al. and Chang et al. references is clearly laid out in the final rejection mailed 6/4/03..